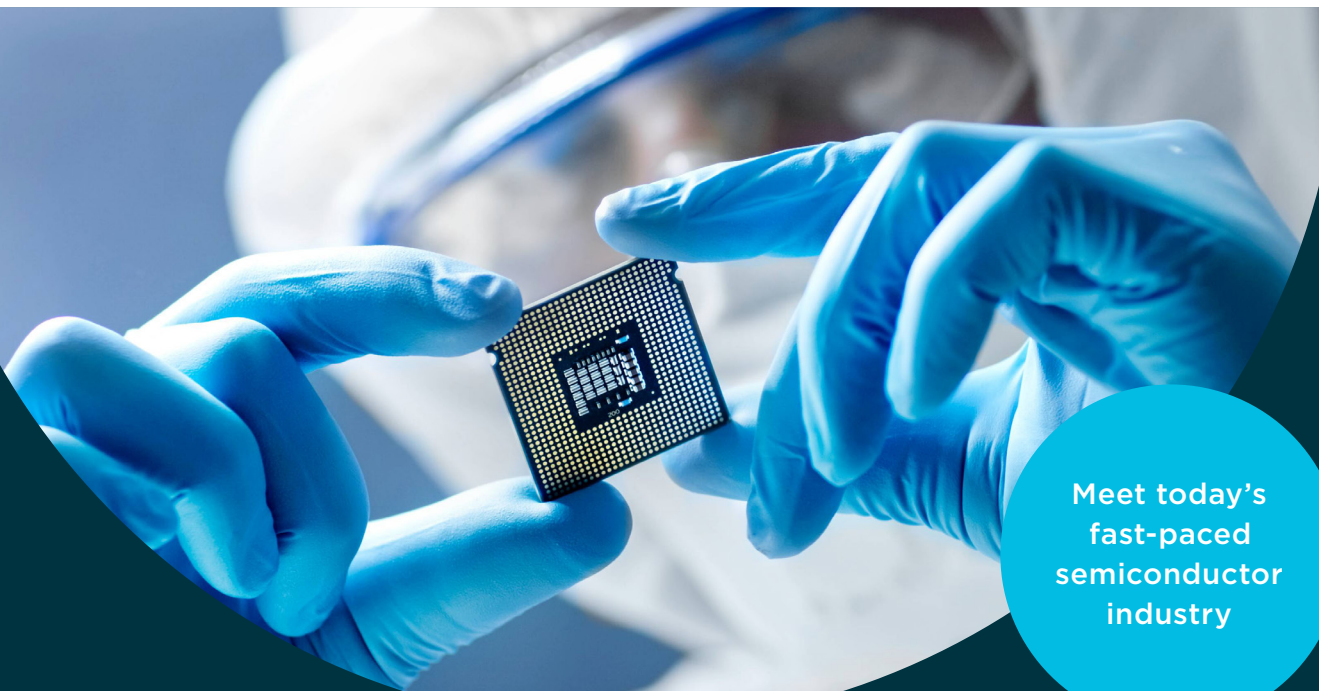
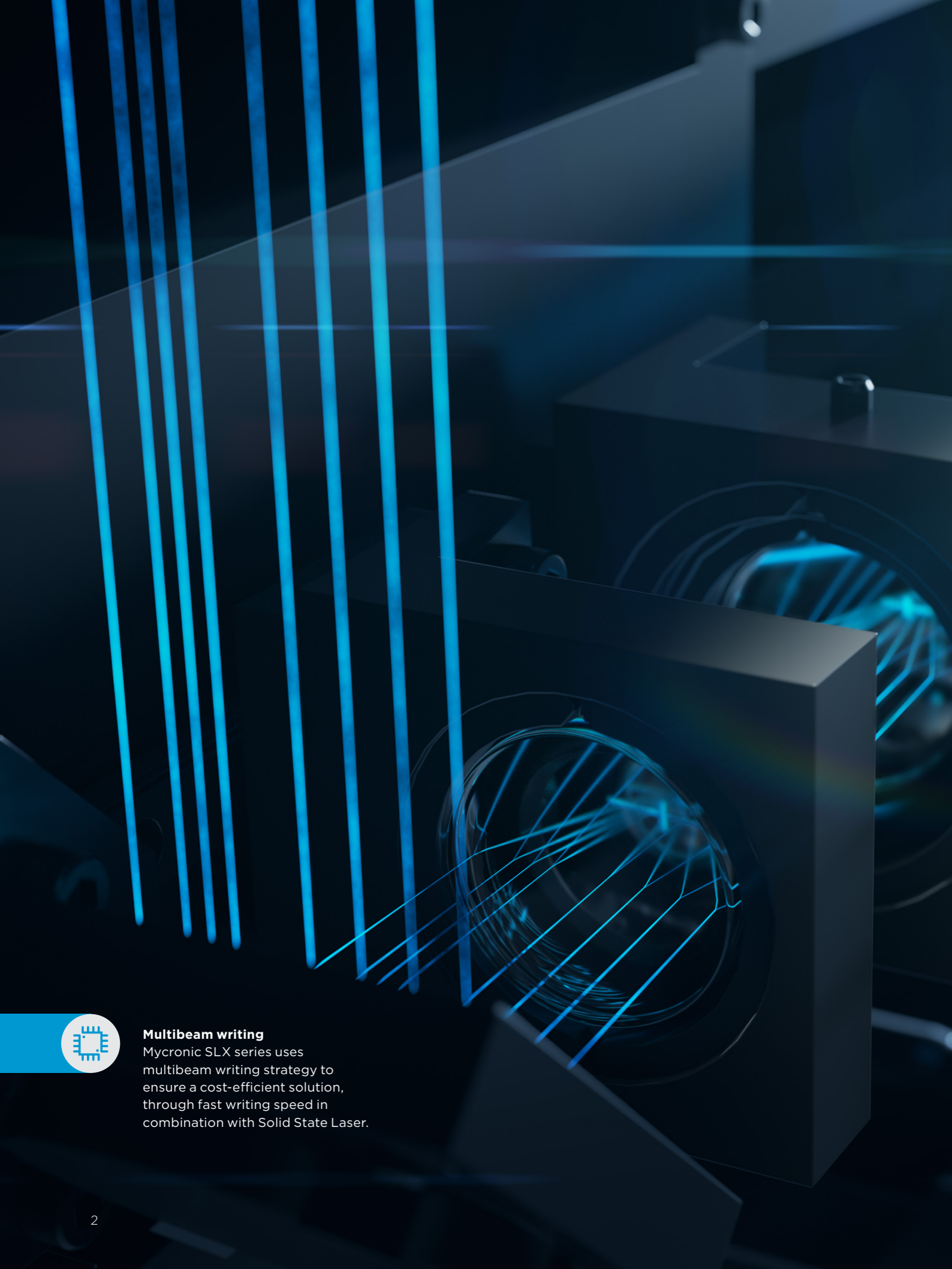


Built for a smarter **digital future**

The new SLX™ series



Meet today's
fast-paced
semiconductor
industry



Multibeam writing

Mycronic SLX series uses multibeam writing strategy to ensure a cost-efficient solution, through fast writing speed in combination with Solid State Laser.

Mycronic SLX series

Gear up to meet today's fast-paced semiconductor industry

Born out of the rising demand of everyday electronics and devices, the SLX laser mask writer is designed to meet the trend towards making everything smarter: consumer goods, cars, Internet of Things, medical devices, and even industrial manufacturing equipment.

By combining field-proven technology, modern datapath management and state-of-the-art optics, the SLX operates faster, more reliably and at a lower cost of ownership - all throughout its lifecycle. Out of the over 600,000 photomasks produced in the semiconductor industry each year, 70-75% of these are written using laser-based mask writers. Most systems have been in service for some 15-25 years, making production slow and costly, with machines difficult to maintain. In short - these are rapidly approaching their replacement cycle.

WHAT YOU'LL GET WITH THE SLX SERIES

- Low cost of ownership with a wide range of configuration choice
- Stable and fast data preparation to support ever increasing data sizes
- A reliable system and access to good support
- New modern extendable architecture to enable future needs and functions

THE BEST CHOICE FOR COST-EFFICIENT PRODUCTION

Due to speed and lower dollar-to-mask costs, laser photo masks are preferred whenever they can meet the technical requirements. By applying writing principles proven from Mycronics' display systems, the SLX series provides unrivaled writing speed compared to existing systems in the field, where our fastest SLX model can expose 6" photomask within just minutes.

SLX is also equipped with Solid State Laser, cutting the power consumption with over 90% compared to the majority of lasers used in the market today.



MCMC
enables
real-time
compensation
to minimize
deviation

WIDE RANGE OF CONFIGURATION OFFERING

Different customers have different technical requirements depending on applications and production mix. The SLX series offers three different base models which can be further customized, adding a wide range of options.

- **SLX 1:** the high-throughput i-line model delivers utmost productivity for lower-end semiconductor nodes
- **SLX 2:** a well-balanced i-line model for users who aim for both productivity and higher semiconductor nodes
- **SLX Lite 3:** a DUV model optimized for Phase Shift Mask application
- **SLX 3:** the most advanced DUV model, addressable up to around 90 nm node

MODERN DATAPATH MANAGEMENT

One of the critical areas the mature semiconductor market is to have fast, stable and reliable pattern data management design, since the pattern density continues to increase at the same time it requires more compensation. The SLX series modern scalable datapath architecture handles all these aspects by having the same architecture as our state-of-the-art display mask writers that has been continuously

developed over time. All critical processing is done offline, leaving only the data transfer step online to minimize the chance of errors during exposure.

SHARED PLATFORM TECHNOLOGY FOR ULTIMATE SYSTEM RELIABILITY

SLX series are built on Evo control platform which is also used for other Mycronic's mask writers. All movement in the Evo control platform are controlled by a new servo board called MCMC (Multi Channel Motion Control) that enables real-time compensation to minimize deviation. The result is great stability and accuracy - something that's already been proven in the field.

The MCMC servo board also comes with great logging capability, ready to log all motions within the system during exposure with high sampling rate. The log can be analyzed and used for system trending, preventive maintenance and much more, enabling stable system operation and extension to big data applications. Adding to that, the user can customize the machine to further improve system performance and enhance usability to widen the addressable applications.



KEY HIGHLIGHTS

- Wide range of configuration options built on modern platform
- Unprecedented writing speed utilizing parallelized multibeam exposure
- Solid State Laser to cut down power consumption and environment-friendly
- Field proven offline datapath with write time independent of pattern complexity
- Access to skilled service from day one for stable and optimized operation
- Contamination free and reliable platform with unmatched uptime



Rewriting the standard of high-volume production

The SLX series, with superior writing speed and modern datapath management, it's made to rewrite the standard of high-volume production.



SLX 1 e1

KEY SPECIFICATIONS	2 PASS	1 PASS
Writing speed*	~40 mins	~20 mins
Minimum Line Width	700 nm	700 nm
CD Uniformity (3σ)	25 nm	35 nm
Registration (3σ)	30 nm	40 nm
2 nd layer alignment (mean + 3σ)	60 nm	100 nm
Laser wavelength	404 nm	

SLX 2 e1

KEY SPECIFICATIONS	3 PASS	2 PASS	1 PASS
Writing speed*	~90 mins	~60 mins	~30 mins
Minimum Line Width	500 nm	500 nm	550 nm
CD Uniformity (3σ)	12 nm	15 nm	20 nm
Registration (3σ)	20 nm	25 nm	30 nm
2 nd layer alignment (mean + 3σ)	45 nm	50 nm	60 nm
Laser wavelength	404 nm		

SLX LITE 3 e1

KEY SPECIFICATIONS	3 PASS	2 PASS	1 PASS
Writing speed*	~123 mins	~82 mins	~41 mins
Minimum Line Width	450 nm	450 nm	500 nm
CD uniformity (3σ)	12 nm	15 nm	20 nm
Registration (3σ)	20 nm	25 nm	30 nm
2 nd layer alignment (mean + 3σ)	30 nm	45 nm	60 nm
Laser wavelength	266 nm		

SLX 3 e1

KEY SPECIFICATIONS	3 PASS	2 PASS	1 PASS
Writing speed*	~180 mins	~120 mins	~60 mins
Minimum Line Width	400 nm	400 nm	400 nm
CD Uniformity (3σ)	10 nm	12 nm	20 nm
Registration (3σ)	20 nm	25 nm	20 nm
2 nd layer alignment (mean + 3σ)	30 nm	45 nm	60 nm
Laser wavelength	266 nm		

* Estimate exposure time with XT mode for 6" mask with area 150 mm x 150 mm

Bringing tomorrow's electronics to life

MYCRONIC

MYCRONIC.COM

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